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(54) Title: SOLUTION SUPPLY DEVICE AND SEMICONDUCTOR APPARATUS

(54) 发明名称: 溶液供给装置及半导体设备

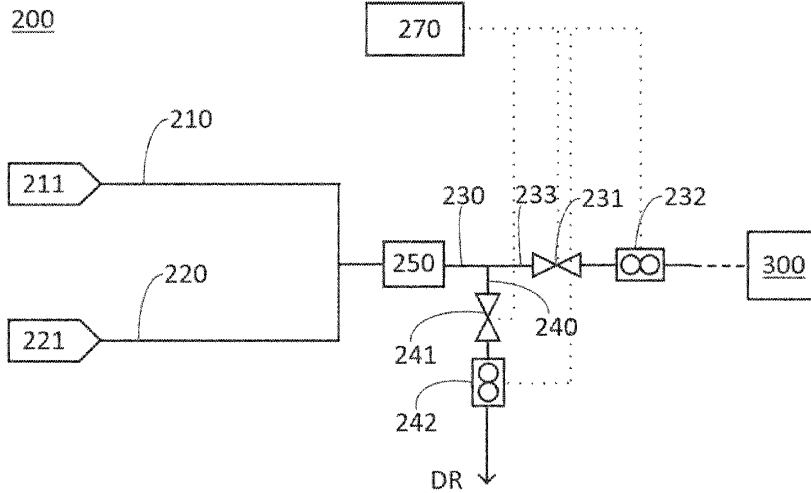


图 2

(57) Abstract: Disclosed in the present invention are a solution supply device and a semiconductor apparatus. The solution supply device is used for providing a mixed solution for a treatment device, and comprises: a first solution input end; a second solution input end; a first conveying pipeline; a second conveying pipeline; a mixing tank, which is arranged at the junction of the first conveying pipeline and the second conveying pipeline; a main conveying pipeline, which is connected to the mixing tank; a main discharge pipeline, which is connected to the main conveying pipeline between the mixing tank and the treatment device; and a control component, which is in communication connection with the main discharge pipeline and the main conveying pipeline, wherein the control component is

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used for making the solution, which has unstable flow, be discharged through the main discharge pipeline before the main conveying pipeline provides the mixed solution for the treatment device. By means of the present invention, the effect of improving the precision of volume proportions of chemical components in the mixed solution is achieved.

(57) 摘要: 本发明公开了溶液供给装置及半导体设备, 该溶液供给装置用于为处理装置提供混合溶液, 包括: 第一溶液输入端、第二溶液输入端、第一输送管线、第二输送管线、设于第一和第二输送管线汇合处的混合槽、与混合槽连接的主输送管线、连接于混合槽和处理装置之间的主输送管线的主排放管线, 以及与主排放管线和主输送管线通信连接的控制部件, 该控制部件用于使主输送管线为处理装置提供混合溶液之前, 经主排放管线排放具有不稳定流量的溶液。本发明实现了提升混液中各化学组分的体积比例精度的效果。